

UNITED S S DEPARTMENT OF COMMERCE Patent and Trademark Office Address: COMMISSIONER OF PATENTS AND TRADEMARKS Washington, D.C. 20231

	11/27/96	MISHRA		U	30794.12US01
APPLICATION NUMBER	FILING DATE		ED APPLICANT		ATTY, DOCKET NO.
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		OFFICE ACTION	SUMMARY		
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Responsive to communic	cation(s) filed on	4/4/19	<u> </u>	·	
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This action is FINAL.					
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Since this application is i	n condition for allowa	nce except for formal m	natters, prosecution as	to the merits	Is closed in
accordance with the prac	ctice under Ex parte C	<i>luayle</i> , 1935 D.C. 11; 4	53 O.G. 213		
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shortened statutory period	for response to this a	ction is set to expire		_ month(s), or	
hichever is longer, from the	mailing date of this co	ommunication. Failure	to respond within the pe	riod for respon	ise will cause
e application to become ab-	andoned. (35 U.S.C.	§ 133). Extensions of	time may be obtained ui	nder the provis	ions of 37 CFR
136(a).					
Isposition of Claims	1	_			
Claim(s)	1-10 1	7-20		is/are nen	ding in the application.
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Of the above, claim(s)		11-1	.0	∡s#are withdra\	wn from consideration.
Claim(s)					is/are allowed.
Claim(s) 1 —	10,17-2	0			→ss/are rejected.
Claim(s)					is/are objected to.
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See the attached Notice	,	•	•	the Everiner	
The drawing(s) filed on _				_ ·	
The proposed drawing of	orrection, filed on			is 🔲 approve	d 🔲 disapproved.
The specification is object	cted to by the Examin	er.			
The oath or declaration is	•				
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riority under 35 U.S.C. § 1	19				
Acknowledgment is mad	e of a claim for foreig	n priority under 35 U.S.	C. § 119(a)-(d).		
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All Some*	None of the CERTI	IFIED copies of the pric	ority documents have be	en	
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Notice of Befores Cite	M DTO 902				•
Notice of Reference Cite	ea, P10-892				
Information Disclosure S	statement(s), PTO-144	19, Paper No(s)			
Interview Summary, PTC	D-413				

-- SEE OFFICE ACTION ON THE FOLLOWING PAGES--

Notice of Draftperson's Patent Drawing Review, PTO-948

Notice of Informal Patent Application, PTO-152

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Art Unit: 1107

Part III DETAILED ACTION

Applicant's election with traverse of group ii in Paper No. 3 is acknowledged. The traversal is on the ground(s) that the process for semiconductor layer can not be used to a materially different product. This is not found persuasive because the product claim it is not necessary how the product is made because the same product can be made in number ways such as formation III-nitride layer can be produced by different process such as using plasma instead of using ultraviolet light for ionization.

The requirement is still deemed proper and is therefore made FINAL.

Specification:

In page 6, line 17 the disclosure of formula for arsene is irrelevant because the invention is nothing to with arsene to form III-nitride layer; in page 7, line 4 disclosing of ammonia is not correct and it should be replace with "mercury".

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-5, 17-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamazaki et al.

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Yamazaki et al discloses a method of making a semiconductor device by photo enhanced chemical vapor deposition by the following process steps;

providing a secondary reactant gas such as ammonia into the chamber;

providing a primary reactant gases such as Ga(cH 3)3;
and then providing ultraviolet light, which is produced from
the mercury lamp, into the chamber and irradiates the reactant
gases to produce reactant ions; then
finally depositing the reactant ions on the surface of the
substrate to form III-nitride layers such as GaN layer(see col.
4, lines 15-33, col 5, lines 30-36, col. 6, lines 47-59).
Yamazaki et al do not disclose particularly dissociation of the
nitrogen molecules into ions by the light emission. It would have
been obvious to one of ordinary skill in the art to understand
the dissociation of nitrogen must have been inherently present in
the invention of Yamazaki et al because Yamazaki et al performs
the process steps as similar to the process steps of instant
invention.

Claims 5-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jp 07291791 document.

Jp 07291791 document discloses forming gallium nitride by using plasma in the chamber with reactant elements to grow epitaxial layers on the substrate(see abstracts and relevant description of Jp 07291791). However, in the reference it is not

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clear whether xenon gas is used for excitation of the nitrogen or not. However, Jp 07291791 clearly disclose excitation cell gives plasma discharge luminous strength to readily excite the nitrogen gas (see advantage). It would have been obvious to one of ordinary skill in the art to understand xenon may be an alternate choice in the invention of Jp 07291791.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Moustakas et al disclose forming III-nitride layer by using plasma.

This office action has been created under the Patent and Trademark Office Semiconductor Technology Quality Assurance Pilot Program. It incorporates the examination quality standards set as a result of customer focus sessions with the semiconductor industry. The listing of the field of search to follow is one of these standards.

Field of Search	Date
U.S. Class and subclass: 437/5,126, 133,129,107,127 148/dig 113 427/582 117/105	6/16/97
Other Documentation: none	
<pre>Electronic data base(s): APS and WPIDS</pre>	6/16/97

Any inquiry concerning this communication or earlier communications from the examiner should be directed to S. Mulpuri whose telephone number is $(703)\ 305-5184$. The fax phone number for this Group is $(703)\ 305-5184$.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (703) 308-0661.

S. Mulpuri

6/16/97

PRIMARY EXAMINER **GROUP 1100**

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